U.S. PATE APPL. NO.: 09/596,837

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Vladimir Vaganov

SERIAL NUMBER: 09/596,837

FILED: June 19, 2000

FOR: Method for Fabricating Microstructures with Deep Anisotropic Etching of Thick Silicon

Wafers

MAY 1 6 2003

PATENT

ART UNIT NO.: 1763

EXAMINER: George Z. Goudreau

ATTORNEY DOCKET NO.: SS-714-01

DATE OF THIS PAPER:

MAY 13, 2003

I hereby certify that this Response and the documents referred to as enclosed therein are being deposited with the United States Postal Service as First Class Mail on May 13, 2003 addressed to Attn: Mail Stop Non-Fee Amendments, Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Debra L. Czapenski

Typed or printed name of person pailing paper or fee

Signature of person mailing paper

GROUP 1700

MAY 2 0 2503

RECEIVED

Attn: Mail Stop Non-Fee Amendments

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

RESPONSE

Sir:

In response to the Office Action mailed March 17, 2003, please amend the above-identified application as follows: